



Figure 1: N Channel MOSFET Level 2 model

Form:

`mosn2:(instance name) n1 n2 n3 n4 <parameter list>`

- n_1 is the drain node,
- n_2 is the gate node,
- n_3 is the source node,
- n_4 is the bulk node.

Parameters:

| Parameter | Type | Default value | Required? |
|--|--------|---------------------|-----------|
| vt0: Zero bias threshold voltage (V) | DOUBLE | 0 | no |
| kp: Transconductance parameter (A/V^2) | DOUBLE | 2×10^{-5} | no |
| gamma: Bulk threshold parameter ($V^{0.5}$) | DOUBLE | 0 | no |
| phi: Surface inversion potential (V) | DOUBLE | 0.6 | no |
| lambda: Channel-length modulation ($1/V$) | DOUBLE | 0 | no |
| rd: Drain ohmic resistance (Ω) | DOUBLE | 0 | no |
| rs: Source ohmic resistance (Ω) | DOUBLE | 0 | no |
| is: Bulk junction saturation current (A) | DOUBLE | 1×10^{-14} | no |
| pb: Bulk junction potential (V) | DOUBLE | 0.8 | no |
| js: Bulk junction saturation current density (A) | DOUBLE | 0 | no |
| tox: Oxide thickness (m) | DOUBLE | 1×10^{-7} | no |
| ld: Lateral diffusion length (m) | DOUBLE | 0 | no |
| u0: Surface mobility ($cm^2/V\cdot s$) | DOUBLE | 600 | no |
| fc: Forward bias junction fit parameter | DOUBLE | 0.5 | no |
| nsub: Substrate doping (cm^{-3}) | DOUBLE | 1×10^{15} | no |
| tpg: Gate material type | DOUBLE | 1 | no |
| nss: Surface state density (cm^{-2}) | DOUBLE | 0 | no |
| delta: Width effect on threshold | DOUBLE | 0 | no |
| uexp: Crit. field exp for mob. deg. | DOUBLE | 0 | no |
| ucrit: Crit. field for mob. degradation | DOUBLE | 1×10^4 | no |
| vmax: Maximum carrier drift velocity | DOUBLE | 0 | no |
| xj: Junction depth | DOUBLE | 0 | no |
| neff: Total channel charge coeff. | DOUBLE | 1 | no |
| nfs: Fast surface state density | DOUBLE | 0 | no |
| tnom: Nominal temperature (C) | DOUBLE | 27 | no |
| kf: Flicker noise coefficient | DOUBLE | 0 | no |
| af: Flicker noise exponent | DOUBLE | 1 | no |
| t: Device temperature (C) | DOUBLE | 27 | no |
| l: Device length (m) | DOUBLE | 2×10^{-6} | no |
| w: Device width (m) | DOUBLE | 50×10^{-6} | no |
| alpha: Impact ionization current coefficient | DOUBLE | 0 | no |

Example:

mosn2:m1 2 3 0 0 l=1.2u w=20u

Description:

*f*REEDA[™] has the NMOS level 2 model based on the MOS level , Grove-Frohman model in SPICE. The model uses the charge conservative Yang-Chatterjee model for modeling charge and capacitance.

Notes:

This is the M element in the SPICE compatible netlist. The unmodified Yang-Chatterjee charge model has a charge partition scheme in the saturation region that sets the drain charge to zero. This results in a loss of the high-frequency current roll-off at the drain node in saturation.

Version:

2002.08.01

Credits:

| Name | Affiliation | Date | Links |
|--------------|---------------------|-------------|--|
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